

23672 EXPEDITED HANDLING BOX AF

IN THE U.S. PATENT AND TRADEMARK OFFICE

Inventor Bernd RECH et al

Patent App. 10/587,130

Filed 28 December 2007

Conf. No. 3123

For TRANSPARENT AND CONDUCTIVE OXIDE LAYER,  
PRODUCTION AND....

Art Unit 1795

Examiner Berman, J

Hon. Commissioner of Patents

Mail Stop AF

Box 1450

Alexandria, VA 22313-1450

FIFTH AMENDMENT - AFTER FINAL ACTION

This is in response to the Office Action mailed  
03 September 2010.

The claims stand rejected on a combination of three new  
references, namely US 6,107,16 of Kariya, US 6,537,428 of Xiong,  
and US 2002/0190814 of Yamada.

Kariya uses sputtering to prepare ZnO from ceramic  
targets at high temperatures with low F doping (0.1-10t). This  
reference further mentions the possibility of reactive sputtering,  
but does not go into details on working points or lower deposition  
rate at high substrate temperature as observed by others (Szyszk